

AMENDMENTS TO THE SPECIFICATION

Please amend paragraph 4 as follows:

[004] Maskless lithography may use electrons, ions or electromagnetic radiation for writing on the substrate. In either case, modulators for modulating the writing signal intensities are needed. In case of electromagnetic radiation in the UV or visible wavelength region, each maskless lithography system includes a light modulator. Systems that utilize multiple light beams include a modulator that is capable of modulating many light beams simultaneously. There are two types of light modulator, the first one is reflective and the second is diffractive. Both include modulation elements, such as movable micro-mirrors that may be moved/manipulated such as to direct an incident light beam a certain direction. A common prior art modulator can turn each of its modulating elements "on" (the light ~~beam~~ beam is directed towards the substrate) or "off" (the light beam is reflected away from the substrate) and is referred to as a binary modulator. Such a modulator is manufactured by Texas Instruments and is known as DMD.